

Begin	End	Duration	Title	Speaker	Affiliation
9:00	9:05	0:05	Opening		
9:05	9:05	0:00	Session 1		
9:05	9:40	0:35	Invited 1 : Embedded Flash Technologies: Enabler for Automotive μCs & Smartcards	Robert Strenz	Infineon
9:40	10:00	0:20	Talk 1 : Split-gate charge trap memories: impact of scaling on performances and consumption for low-power embedded applications	Lia Masoero	Leti
10:00	10:20	0:20	Talk 2 : Ab initio simulation applied to innovative memory devices	Philippe Blaise	Leti
10:20	10:55	0:35	Invited 2 : Embedded non volatile memories for consumer applications: status and perspectives	Paola Zuliani	ST
10:55	11:15	0:20	Break		
11:15	11:15	0:00	Session 2		
11:15	11:50	0:35	Invited 3 : Phase-change memories for energy-efficient data-centric IT applications	Agostino Pirovano	Micron
11:50	12:10	0:20	Talk 3 : Phase change materials engineering for reset current reduction.	Véronique Sousa	Leti
12:10	12:30	0:20	Talk 4 : Study of GST nanosized clusters	Giada Ghezzi	Leti
12:30	12:50	0:20	Talk 5 : Magnetic memory for hybrid CMOS electronics	Ricardo Sousa	INAC/Spintec
12:50	14:20	1:30	Lunch		
14:20	14:20	0:00	Session 3		
14:20	14:55	0:35	Invited 4 : Phase Change Memory: Replacement or Transformational	Hsiang-Lan Lung	Macronix
14:55	15:15	0:20	Talk 6 : Resistive switching concept: a new design paradigm	Jean-Michel Portal	IM2NP
15:15	15:35	0:20	Talk 7 : Using OxRAM for saving power in FPGA architecture: what can we expect?	Fabien Clermidy	Leti
15:35	15:55	0:20	Talk 8 : PCM for Neuromorphic applications	Manan Suri	Leti
15:55	16:15	0:20	Talk 9 : Experimental investigation and empirical modeling of the set and reset kinetics of Ag-GeS ₂ Conductive Bridging Memories	Elisa Vianello	Leti
16:15	16:35	0:20	Break		
16:35	16:35	0:00	Session 4		
16:35	17:10	0:35	Invited 5 : Resistive Memory Technology for High Density Memory Applications.	Sunjung Kim	Samsung
17:10	17:30	0:20	Talk 10 : Characterization and Modelling of Electrode Impact in HfO ₂ -based RRAM	Carlo Cagli	Leti
17:30	17:50	0:20	Talk 11 : In-operando HAXPES as a non-destructive technique for investigating the resistive switching phenomenon	Thomas Bertaud	IHP
17:50	18:10	0:20	Talk 12 : Study of ReRAM based on TiN/ TaO _y /TiN integrated into a 65nm advanced CMOS technology	Thérèse Diokh	ST
18:10	18:15	0:05	Conclusions		